

	Hits	Search Text	DBs
47	2	<p>((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3 or platen) same (photosensitive or photoresist or resist)) and (pattern\$4 same (mask or reticle or photomask)) and (plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV or laser or (projection near9 system)) and (gas\$3 same (plasma or ion\$3beam or beam or laser or ion\$4assist\$5 or ion\$4beam) same ((perchlorinated or perbrominated or periodinated or chloro or bromo or iodo or chlorine or iodine or bromine or halogen or (halogenated near9 alkane) or perhalogenat\$3) near29 (alkane or methane or ethane or propane or butane or pentane)))</p>	<p>US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB</p>

	Hits	Search Text	DBs
48	26	((substrate or wafer or device or workpiece) same (photosensitive or photoresist or resist) same (expos\$4 or irradiat\$4 or illuminat\$4)) and (plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV or laser or (projection near9 system)) and (gas\$3 same (plasma or ion\$3beam or beam or laser or ion\$4assist\$5 or ion\$4beam) same ((perchlorinated or perbrominated or periodinated or chloro or bromo or iodo or chlorine or iodine or bromine or halogen or (halogenated near9 alkane) or perhalogenat\$3) near29 (alkane or methane or ethane or propane or butane or pentane)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
49	30	((substrate or wafer or device or workpiece) same (photosensitive or photoresist or resist) same (expos\$4 or irradiat\$4 or illuminat\$4)) and (plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV or laser or (projection near9 system) or (collector near12 optics) or (light near12 source)) and ((gas\$3 or etchant) same (plasma or ion\$3beam or beam or laser or ion\$4assist\$5 or ion\$4beam or ions) same ((perchlorinated or perbrominated or periodinated or chloro or bromo or iodo or chlorine or iodine or bromine or halogen or (halogenated near9 alkane) or perhalogenat\$3) near29 (alkane or methane or ethane or propane or butane or pentane)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
50	41	((substrate or wafer or device or workpiece) same (photosensitive or photoresist or resist) same (expos\$4 or irradiat\$4 or illuminat\$4)) and ((plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV or laser or (projection near9 system) or (collector near12 optics) or (light near12 source)) same (gas\$3 or etchant or plasma or ion\$3beam or beam or laser or ion\$4assist\$5 or ion\$4beam or ions) same ((perchlorinated or perbrominated or periodinated or chloro or bromo or iodo or chlorine or iodine or bromine or halogen or (halogenated near9 alkane) or perhalogenat\$3) near29 (alkane or methane or ethane or propane or butane or pentane)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
51	15	S50 NOT S48	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
52	2	((substrate or wafer or device or workpiece) same (photosensitive or photoresist or resist) same (expos\$4 or irradiat\$4 or illuminat\$4)) and ((plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV or laser) same ((projection near9 system) or (collector near12 optics) or (light near12 source)) same (gas\$3 or etchant or plasma or ion\$3beam or beam or laser or ion\$4assist\$5 or ion\$4beam or ions) same ((perchlorinated or perbrominated or periodinated or chloro or bromo or iodo or chlorine or iodine or bromine or halogen or (halogenated near9 alkane) or perhalogenat\$3) near29 (alkane or methane or ethane or propane or butane or pentane)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
53	1	((substrate or wafer or device or workpiece) same (photosensitive or photoresist or resist) same (expos\$4 or irradiat\$4 or illuminat\$4)) and ((plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV or laser) same ((projection near9 system) or (collector near12 optics) or (light near12 source)) same (gas\$3 or etchant or plasma or ion\$3beam or beam or laser or ion\$4assist\$5 or ion\$4beam or ions) same ((perchlorinated or perbrominated or periodinated or chloro or bromo or iodo or chlorine or iodine or bromine or halogen or (halogenated near9 alkane) or perhalogenat\$3) near29 (alkane or methane or ethane or propane or butane or pentane)))	US-PGPUB

	Hits	Search Text	DBs
54	6	((plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV or laser) same ((projection near9 system) or (collector near12 optics) or (light near12 source)) same (gas\$3 or etchant or plasma or ion\$3beam or beam or laser or ion\$4assist\$5 or ion\$4beam or ions) same ((perchlorinated or perbrominated or periodinated or carbontetrachloride or tetrachloromethane or tetrabromomethane or carbontetrabromide or carbontetraiodide or trichloromethane or tribromomethane or triiodomethane or chloro or bromo or iodo or chlorine or iodine or bromine or halogen or (halogenated near9 alkane) or perhalogenat\$3) near29 (alkane or methane or ethane or propane or butane or pentane)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hit s	Search Text	DBs
55	6	((plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV or laser) same ((projection near9 system) or (collector near12 optics) or (light near12 source) or (cleaning near12 optics)) same (gas\$3 or etchant or plasma or ion\$3beam or beam or laser or ion\$4assist\$5 or ion\$4beam or ions) same ((perchlorinated or perbrominated or periodinated or carbontetrachloride or tetrachloromethane or tetrabromomethane or carbontetrabromide or carbontetraiodide or trichloromethane or tribromomethane or triiodomethane or chloro or bromo or iodo or chlorine or iodine or bromine or halogen or (halogenated near9 alkane) or perhalogenat\$3) near29 (alkane or methane or ethane or propane or butane or pentane)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB



	Hits	Search Text	DBs
56	15	(((projection near9 system) or (collector near12 optics) or (light near12 source) or (cleaning near12 optics)) same (gas\$3 or etchant or plasma or ion\$3beam or beam or laser or ion\$4assist\$5 or ion\$4beam or ions or radiation) same ((perchlorinated or perbrominated or periodinated or carbontetrachloride or tetrachloromethane or tetrabromomethane or carbontetrabromide or carbontetraiodide or trichloromethane or tribromomethane or triiodomethane or chloro or bromo or iodo or chlorine or iodine or bromine or halogen or (halogenated near9 alkane) or perhalogenat\$3) near29 (alkane or methane or ethane or propane or butane or pentane)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
57	104	((gas\$3 or etchant or plasma or ion\$3beam or beam or laser or ion\$4assist\$5 or ion\$4beam or ions or radiation) same ((fluorine or perchlorinated or perbrominated or periodinated or carbontetrachloride or tetrachloromethane or tetrabromomethane or carbontetrabromide or carbontetraiodide or trichloromethane or tribromomethane or triiodomethane or chloro or bromo or iodo or chlorine or iodine or bromine or halogen or (halogenated near9 alkane) or perhalogenat\$3) near29 (alkane or methane or ethane or propane or butane or pentane)) same (cleaning or contamination))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

58	122	((gas\$3 or etchant or plasma or ion\$3beam or beam or laser or ion\$4assist\$5 or ion\$4beam or ions or radiation) same ((fluorine or perchlorinated or perbrominated or periodinated or carbontetrachloride or tetrachloromethane or tetrabromomethane or carbontetrabromide or carbontetraiodide or trichloromethane or tribromomethane or triiodomethane or chloro or bromo or iodo or chlorine or iodine or bromine or chlorofluorocarbon or flons or halogen or (halogenated near9 alkane) or perhalogenat\$3) near29 (alkane or methane or ethane or propane or butane or pentane)) same (cleaning or contamination))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
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	Hits	Search Text	DBs
59	18	S59 NOT S58	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
60	104	S59 NOT S60	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
61	103	((gas\$3 or etchant or plasma or ion\$3beam or beam or laser or ion\$4assist\$5 or ion\$4beam or ions or radiation) same ((perchlorinated or perbrominated or periodinated or carbontetrachloride or tetrachloromethane or tetrabromomethane or carbontetrabromide or carbontetraiodide or trichloromethane or tribromomethane or triiodomethane or chloro or bromo or iodo or chlorine or iodine or bromine or chlorofluorocarbon or flons or halogen or (halogenated near9 alkane) or perhalogenat\$3) near29 (alkane or methane or ethane or propane or butane or pentane)) same (cleaning or contamination))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hit s	Search Text	DBs
62	86	((gas\$3 or etchant or plasma or ion\$3beam or beam or laser or ion\$4assist\$5 or ion\$4beam or ions or radiation) same ((perchlorinated or perbrominated or periodinated or carbontetrachloride or tetrachloromethane or tetrabromomethane or carbontetrabromide or carbontetraiodide or trichloromethane or tribromomethane or triiodomethane or chloro or bromo or iodo or chlorine or iodine or bromine or chlorofluorocarbon or flons) near29 (alkane or methane or ethane or propane or butane or pentane)) same (cleaning or contamination))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
63	154	((gas\$3 or etchant or plasma or ion\$3beam or beam or laser or ion\$4assist\$5 or ion\$4beam or ions or radiation) same ((perchlorinated or perbrominated or periodinated or carbontetrachloride or tetrachloromethane or tetrabromomethane or carbontetrabromide or carbontetraiodide or trichloromethane or tribromomethane or triiodomethane or chlorine or iodine or bromine or chlorofluorocarbon) near29 (alkane or methane or ethane or propane or butane or pentane or (carbon near12 compound))) same (clean\$4 or ((contamination or residual or soot) near19 (remov\$4 or blast\$4 or strip\$4 or etch\$3))))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hit s	Search Text	DBs
64	86	((gas\$3 or etchant or plasma or ion\$3beam or beam or laser or ion\$4assist\$5 or ion\$4beam or ions or radiation) same ((perchlorinated or perbrominated or periodinated or carbontetrachloride or tetrachloromethane or tetrabromomethane or carbontetrabromide or carbontetraiodide or trichloromethane or tribromomethane or triiodomethane or chloro or bromo or iodo or chlorine or iodine or bromine or chlorofluorocarbon or flons) near29 (alkane or methane or ethane or propane or butane or pentane)) same (cleaning or contamination))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
65	104	S64 NOT S65	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
66	18	((gas\$5 or plasma or ion or beam or radiation) same ((perchlorinated or carbontetrachloride or tetrachloromethane or tetrabromomethane or chloroalkanes or chlor\$5hydrocarbons or chloromethane trichloromethane or chlorofluorocarbon) near29 (alkane or methane or ethane or propane or butane or pentane or (carbon near12 compound))) same (clean\$4 or remov\$4 or blast\$4 or strip\$4 or etch\$3) near16 (reactor or chamber or wall or surface))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
67	23	((perchlorinated or carbontetrachloride or tetrachloromethane or tetrabromomethane or chloroalkanes or chlor\$5hydrocarbons or chloromethane trichloromethane or chlorofluorocarbon) near29 (alkane or methane or ethane or propane or butane or pentane or (carbon\$6 near12 compound))) same (clean\$4 or remov\$4 or blast\$4 or strip\$4 or etch\$3 or roughening or bombarding) near16 (reactor or chamber or wall or surface))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB